

PHOTOSENSITIVE RESIN COMPOSITION, PHOTOSENSITIVE RESIN
SHEET, CURED PRODUCT, HOLLOW STRUCTURE, ELECTRONIC
COMPONENT, AND ELASTIC WAVE FILTER

ABSTRACT

The purpose of the present invention is to provide a photosensitive resin composition having excellent pattern processability and pressure resistance. The present invention is a photosensitive resin composition comprising (A) a polymer, (B) a radically polymerizable compound, (C) a photopolymerization initiator, and (D) an inorganic filler, wherein the radically polymerizable functional group equivalent of the (B) radically polymerizable compound is 70-200 g/eq or less on average.

[No suitable figure]